

ALC '03



4th International Symposium on Atomic Level Characterizations for New Materials and Devices

OCT. 5 - 10, 2003

Radisson Kauai Beach Resort, KAUAI, HAWAII, USA

Invited Speakers

G. A. Somorjai

A. Tonomura

M. Altman

M. Aono

E. Bauer

M. Bode

H. H. Brongersma

B. L. Doyle

C. S. Fadley

Y. Fujikawa

T. Fujimoto

M. Giessen

T. Gustafsson

W. Heiland

A. Heinrich

T. Hirayama

Y. Homma

H. Ibach

M. Inoue

D. C. Joy

H. J. Kang

Y. Kido

M. Kiskinova

S. Kono

T. Koshikawa

H. Lichte

J. -J. Metois

E. Meyer

J. Miao

B. Mizuno

R. Morin

S. Morita

H. Neddermeyer

Y. Nihei

A. Nishiyama

N. Osakabe

C. Oshima

J. Osterwalder

A. Pavlovskaya

R. Palmer

J. W. Rabalais

K. -H. Rieder

H. Rose

M. Schleberger

T. Schmidt

W. -D. Schneider

Y. Takai

H. Takenaka

T. T. Tsong

P. Varga

Q. -K. Xue

Y. Zhu

Tutorial Sessions

E. Bauer

T. Ichinokawa

A. Lucas

D. Newbury

P. W. Palmberg

R. Shimizu

O. C. Wells

D. Williams

Session Topics

LEEM/PEEM

Coherent electron source

Photoelectron diffraction & holography

50 years anniversary of Bi-prism

SPM & atomic/molecular manipulation

Instrumentation

Surface/Interface phenomena

Surface/Interface analysis

Ion beam

TEM & REM

Nanodevices

High depth characterization

of High-k materials

Low damage high depth resolution

by low energy ion sputtering

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